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## Hard Self-Iubricating Nanocomposite PVD Coatings for Space and Terrestrial Applications

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## <u>Outlook</u>

- 1. Why using solid lubrication in space?
- **2**. Introduction to solid lubrication with MoS<sub>2</sub>
- **3**.  $MoS_2$  PVD thin films specific problems
- 4.  $MoS_2$  + hard phase: possible combinations
- 5. Experimental
- **6.**  $MoS_2$  + hard phase: mixed coatings
  - 1. Structure
  - 2. Tribology
- 7. Concluding remarks

#### Because:

- 1. Wide variations in temerature in space fluid lubricants change viscosity, freeze, evaporate, crack.
- 2. Significant radiation (UV, gamma, etc.) fluid lubricants change chemistry.
- **3**. Vacuum fluid lubricants evaporate.

## Introduction to solid lubrication with MoS<sub>2</sub>



can slide easily over each other.



**Problem 1.** Orientation of the (002) planes

#### **Basal – good tribological** properties

Edge – bad tribological properties



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**Problem 2.** Adhesion due to the presense of the (002) planes



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**Problem 3.** Oxidation at the edges of the (002) planes

 $2MoS_2 + 7O_2 \rightarrow 2MoO_3 + 4SO_2 \quad ; \\ 2MoS_2 + 4H_2O + O_2 \rightarrow 2MoO_3 + 4H_2S$ 



Solution: minimisation of the existence of (002) planes, especially edge ones by:

- 1. Deposition at conditions allowing only basal crystallisation
- 2. Alloying MoS<sub>2</sub> with metals and compounds (amorphisation)



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#### MoS<sub>x</sub> + hard phase: possible combinations



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Method for deposition: UnBallanced Magnetron (UBM) Radio Frequency (RF) non-reactive sputtering

Methods for investigation:

- Structure and chemistry: 200 kV Transmission Electron Microscope (TEM) equipped with Energy Dispersive X-ray (EDX) spectrometer
- Tribological characteristics: rotational Pin-On-Disk (POD) tribometer
- Hardness: Nano Hardness Tester (NHT)
- Adhesion: Micro Scratch Tester (MST)

## **Experimental**



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Deposition conditions:	MoS <sub>2</sub> segments	Мо	S	(TiN <sub>y</sub> )	MoS <sub>x</sub> mol.%
	2	14	20	66	17.5
Substrate bias: grounded	3	17	34	49	25.8
-	4	25	38	37	40.3
Temperature = 280 °C	5	25	46	29	46.3
Pressure = 0.4 Pa	6	30	48	23	56.6
11033010 - 0.41 a	8	28	54	18	60.9



For tribology and TEM



#### For TEM (multilayers)

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amorpous  $MoS_xTi_yN_z$  solid solution



fcc-Ti<sub>v</sub>N<sub>w</sub>MoS<sub>u</sub> solid solution

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**Test conditions:** Berkovich indentor, 5 mN normal load, penetration depth 80 – 150 nm (< 10% of the coating thickness)



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**Test conditions:**  $\emptyset$  6 mm Al<sub>2</sub>O<sub>3</sub> ball, normal load 5 N, sliding speed 0.1 m/s, radius 5 mm, temperature 24 °C



**Test conditions:**  $\emptyset$  6 mm Al<sub>2</sub>O<sub>3</sub> ball, normal load 5 N, sliding speed 0.1 m/s, radius 5 mm, temperature 24 °C, 50 % RH



N/min, sliding speed 10 mm/min

Critical loads defined as cohesive/adhesive spallation



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 Alloying TiN with MoS<sub>x</sub> changes the structure of the TiN from dense columnar to nanocrystalline. There is a treshold of MoS<sub>x</sub> content below which all the MoS<sub>x</sub> is dissolved in the fcc TiN matrix and the structure becomes dense columnar.

• Alloying TiN with  $MoS_x$  results in coatings with good adherence to the substrate, low friction coefficient and wear rate against alumina counterpart of up to an order of magnitude lower than that of pure TiN. The lowest wear rate is avhieved for the minimum  $MoS_x$  content, being 17.5 mol.%. The hardness of this coating is the same as for the pure TiN.

• The resulting coatings show very promising tribological properties in both high vavuum and Earth atmospheric conditions.

# Thank you for your attention

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